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Exhibit R-2, RDT&E Budget Item Justification: PB 2011 Defense Advanced Research Projects Agency **DATE:** February 2010

APPROPRIATION/BUDGET ACTIVITY 0400: <i>Research, Development, Test & Evaluation, Defense-Wide</i> BA 3: <i>Advanced Technology Development (ATD)</i>	R-1 ITEM NOMENCLATURE PE 0603739E: <i>ADVANCED ELECTRONICS TECHNOLOGIES</i>
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COST (\$ in Millions)	FY 2009 Actual	FY 2010 Estimate	FY 2011 Base Estimate	FY 2011 OCO Estimate	FY 2011 Total Estimate	FY 2012 Estimate	FY 2013 Estimate	FY 2014 Estimate	FY 2015 Estimate	Cost To Complete	Total Cost
Total Program Element	192.686	194.094	197.098	0.000	197.098	151.274	157.386	150.143	149.334	Continuing	Continuing
MT-07: <i>CENTERS OF EXCELLENCE</i>	7.000	7.000	0.000	0.000	0.000	0.000	0.000	0.000	0.000	Continuing	Continuing
MT-12: <i>MEMS AND INTEGRATED MICROSYSTEMS TECHNOLOGY</i>	63.439	77.963	64.496	0.000	64.496	44.150	50.390	50.037	50.095	Continuing	Continuing
MT-15: <i>MIXED TECHNOLOGY INTEGRATION</i>	122.247	109.131	132.602	0.000	132.602	107.124	106.996	100.106	99.239	Continuing	Continuing

A. Mission Description and Budget Item Justification

(U) The Advanced Electronics Technology program element is budgeted in the Advanced Technology Development Budget Activity because it seeks to design and demonstrate state-of-the-art manufacturing and processing technologies for the production of various electronics and microelectronic devices, sensor systems, actuators and gear drives that have military applications and potential commercial utility. Introduction of advanced product design capability and flexible, scalable manufacturing techniques will enable the commercial sector to rapidly and cost-effectively satisfy military requirements.

(U) The MicroElectroMechanical Systems (MEMS) and Integrated Microsystems Technology project is a broad, cross-disciplinary initiative to merge computation and power generation with sensing and actuation to realize a new technology for both perceiving and controlling weapons systems and battlefield environments. MEMS applies the advantages of miniaturization, multiple components and integrated microelectronics to the design and construction of integrated electromechanical and electro-chemical-mechanical systems to address issues ranging from the scaling of devices and physical forces to new organization and control strategies for distributed, high-density arrays of sensor and actuator elements. The MEMS project has three principal objectives: the realization of advanced devices and systems concepts, the development and insertion of MEMS into DoD systems, and the creation of support and access technologies to catalyze a MEMS technology infrastructure.

(U) The goal of the Mixed Technology Integration project is to leverage advanced microelectronics manufacturing infrastructure and DARPA component technologies developed in other projects to produce mixed-technology microsystems. These 'wristwatch size', low-cost, lightweight and low power microsystems will improve the battlefield awareness and security of the warfighter and the operational performance of military platforms. The chip assembly and packaging processes currently in use produce a high cost, high power, large volume and lower performance system. This program is focused on the monolithic integration of mixed technologies to form

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batch-fabricated, mixed technology microsystems 'on-a-single-chip' or an integrated and interconnected 'stack-of-chips'. The ability to integrate mixed technologies onto a single substrate will increase performance and reliability, while driving down size, weight, volume and cost.

(U) The Centers of Excellence project provided funding to finance the demonstration, training and deployment of advanced manufacturing technology at Marshall University and the MilTech Extension program.

B. Program Change Summary (\$ in Millions)

	<u>FY 2009</u>	<u>FY 2010</u>	<u>FY 2011 Base</u>	<u>FY 2011 OCO</u>	<u>FY 2011 Total</u>
Previous President's Budget	199.504	205.912	0.000	0.000	0.000
Current President's Budget	192.686	194.094	197.098	0.000	197.098
Total Adjustments	-6.818	-11.818	197.098	0.000	197.098
• Congressional General Reductions		-0.813			
• Congressional Directed Reductions		-33.005			
• Congressional Rescissions	-3.798	0.000			
• Congressional Adds		7.000			
• Congressional Directed Transfers		0.000			
• Reprogrammings	2.585	0.000			
• SBIR/STTR Transfer	-5.605	0.000			
• Congressional Restoration for New Starts	0.000	15.000	0.000	0.000	0.000
• TotalOtherAdjustments	0.000	0.000	197.098	0.000	197.098

Congressional Add Details (\$ in Millions, and Includes General Reductions)

Project: MT-07: CENTERS OF EXCELLENCE

Congressional Add: *Advanced Flexible Manufacturing*

Congressional Add Subtotals for Project: MT-07

Project: MT-15: MIXED TECHNOLOGY INTEGRATION

Congressional Add: *Center for Autonomous Solar Power*

Congressional Add: *Hybrid Power Generation System*

Congressional Add: *Ultra Low Power Electronics for Special Purpose Computers/Ubiquitous Computing*

	<u>FY 2009</u>	<u>FY 2010</u>
	7.000	7.000
	7.000	7.000
	4.000	0.000
	1.200	0.000
	1.600	0.000

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Congressional Add Details (\$ in Millions, and Includes General Reductions)

	FY 2009	FY 2010
Congressional Add Subtotals for Project: MT-15	6.800	0.000
Congressional Add Totals for all Projects	13.800	7.000

Change Summary Explanation

FY 2009

Decrease reflects SBIR/STTR transfer and Section 8042 rescission of the FY 2010 Appropriations Act offset by internal below threshold reprogramming.

FY 2010

Decrease reflects reductions for the Section 8097 Economic Assumption, execution delays and FY 2010 new starts offset by the FY 2010 Congressional Restoration for New Starts.

FY 2011

Not Applicable

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COST (\$ in Millions)	FY 2009 Actual	FY 2010 Estimate	FY 2011 Base Estimate	FY 2011 OCO Estimate	FY 2011 Total Estimate	FY 2012 Estimate	FY 2013 Estimate	FY 2014 Estimate	FY 2015 Estimate	Cost To Complete	Total Cost
MT-07: <i>CENTERS OF EXCELLENCE</i>	7.000	7.000	0.000	0.000	0.000	0.000	0.000	0.000	0.000	Continuing	Continuing

A. Mission Description and Budget Item Justification

(U) This project provides funding for the Robert C. Byrd Institute for Advanced Flexible Manufacturing at Marshall University. The Byrd Institute provides both a teaching facility and initiatives to local area industries to utilize computer-integrated manufacturing technologies and managerial techniques to improve manufacturing productivity and competitiveness. Training emphasizes technologies to significantly reduce unit production and life cycle costs and to improve product quality.

B. Accomplishments/Planned Program (\$ in Millions)

	FY 2009	FY 2010
Congressional Add: Advanced Flexible Manufacturing <i>FY 2009 Accomplishments:</i> - Assessed the Institute for Advanced Flexible Manufacturing's performance and worked toward transitioning from DoD to state/private support. <i>FY 2010 Plans:</i> - Continue to Assess the Institute for Advanced Flexible Manufacturing's performance and work toward transitioning from DoD to state/private support.	7.000	7.000
Congressional Adds Subtotals	7.000	7.000

C. Other Program Funding Summary (\$ in Millions)

N/A

D. Acquisition Strategy

N/A

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E. Performance Metrics

Specific programmatic performance metrics are listed above in the program accomplishments and plans section.

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COST (\$ in Millions)	FY 2009 Actual	FY 2010 Estimate	FY 2011 Base Estimate	FY 2011 OCO Estimate	FY 2011 Total Estimate	FY 2012 Estimate	FY 2013 Estimate	FY 2014 Estimate	FY 2015 Estimate	Cost To Complete	Total Cost
MT-12: <i>MEMS AND INTEGRATED MICROSYSTEMS TECHNOLOGY</i>	63.439	77.963	64.496	0.000	64.496	44.150	50.390	50.037	50.095	Continuing	Continuing

A. Mission Description and Budget Item Justification

(U) The MicroElectroMechanical Systems (MEMS) and Integrated Microsystems Technology program is a broad, cross-disciplinary initiative to merge computation and power generation with sensing and actuation to realize a new technology for both perceiving and controlling weapons systems and battlefield environments. Using fabrication processes and materials similar to those used to make microelectronic devices, MEMS applies the advantages of miniaturization, multiple components and integrated microelectronics to the design and construction of integrated electromechanical and electro-chemical-mechanical systems. The MEMS program addresses issues ranging from the scaling of devices and physical forces to new organization and control strategies for distributed, high-density arrays of sensor and actuator elements. These issues include microscale power and actuation systems as well as microscale components that survive harsh environments. The microfluidic molecular systems program will develop automated microsystems that integrate biochemical fluid handling capability along with electronics, optoelectronics and chip-based reaction and detection modules to perform tailored analysis sequences to monitor environmental conditions, health hazards and physiological states.

(U) The MEMS program has three principal objectives: the realization of advanced devices and systems concepts; the development and insertion of MEMS into DoD systems; and the creation of support and access technologies to catalyze a MEMS technology infrastructure. These three objectives cut across a number of focus application areas to create revolutionary military capabilities, make high-end functionality affordable to low-end systems and extend the operational performance and lifetimes of existing weapons platforms. The major technical focus areas for the MEMS program are: 1) inertial measurement; 2) fluid sensing and control; 3) electromagnetic and optical beam steering; 4) chemical reactions on chip; 5) electromechanical signal processing; 6) analytical instruments; and 7) thermal management.

B. Accomplishments/Planned Program (\$ in Millions)

	FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
Harsh Environment Robust Micromechanical Technology (HERMIT) (U) The Harsh Environment Robust Micromechanical Technology (HERMIT) program is developing micromechanical devices that can operate under harsh conditions (e.g., under large temperature excursions, large power throughputs, high g-forces, corrosive substances) while maintaining	6.495	3.600	0.000	0.000	0.000

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B. Accomplishments/Planned Program (\$ in Millions)								
				FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
- Improve self-sufficiency by providing a higher value to program users by improved yield and lower manufacturing costs.								
<p>Low Power Micro Cryogenic Coolers (MCC)</p> <p>(U) The Low Power Micro Cryogenic Coolers (MCC) program will attain superior performance in micro-scale devices (e.g. Low Noise Amplifier (LNA's) IR detectors, RF front-ends, superconducting circuits) by cooling selected portions to cryogenic temperatures. The key approach in this program that should allow orders of magnitude power savings is to selectively cool only the needed volume/ device via MEMS-enabled isolation technologies. Such an approach will benefit a large number of applications where performance is determined predominately by only a few devices in a system, e.g., communications where the front-end filter and LNA often set the noise figure; and sensors, where the transducer and input transistor in the sense amplifier often set the resolution. Additionally, this program will develop a high performance chip-scale micropump for efficient fluid distribution within various microsystems. MEMS technology will also be instrumental for achieving micro-scale mechanical pumps, valves, heat exchangers, and compressors, all needed to realize a complete cryogenic refrigeration system on a chip. Transition of this technology is anticipated through industry, which will incorporate elements of the technology in current and future weapon system designs.</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Integrated micro cooler components together with sufficiently isolated devices to-be-cooled to yield a single chip system consuming very little power. - Developed methods to increase compression ratio and pump speeds to MEMS scales. - Decreased size of on-chip vacuum pumps. <p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Improve MEMS-derived thermal isolation microstructures. - Develop improved thermoelectric materials for integration with existing and future MEMS. - Demonstrate turbomolecular pumping. 				8.711	8.223	6.533	0.000	6.533

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B. Accomplishments/Planned Program (\$ in Millions)						
		FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
<ul style="list-style-type: none"> - Demonstrate micromechanical vacuum on a chip with less than 1 Torr operating pressure. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Develop MEMS-based analytical instruments of <math>10^{-6}</math> Torr with a sampling flow rate with on-chip vacuum conditions. 						
<p>Microsystem Integrated Navigation Technology (MINT)</p> <p>(U) The Microsystem Integrated Navigation Technology (MINT) program is developing technology for precision inertial navigation coupled with micro navigation aiding sensors. The MINT program will develop universally reconfigurable microsensors (e.g., for magnetic fields, temperature, pressure) with unmatched resolution and sensitivity. These devices will use the latest in MEMS and photonic technologies to harness perturbations in atomic transitions as the sensing and measuring mechanisms for various parameters. Program transition will occur through industrial performers into future DoD platforms.</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Reduced power and volume requirements. - Developed technologies to harvest power through energy scavenging. <p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Develop and demonstrate micro-fabrication technologies for creating new classes of MEMS navigation instruments that can be used for achieving high accuracy, GPS free navigation using zero-velocity updating. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Initiate measurements and testing of initial MINT navigation prototypes at DoD laboratories to confirm navigation properties and accuracies. 		5.991	6.687	6.549	0.000	6.549
Integrated Primary Atomic Clock (IMPACT)		7.970	6.916	7.796	0.000	7.796

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B. Accomplishments/Planned Program (\$ in Millions)						
<p>which they are rotating. This program will explore ways at pushing the envelope by engineering ways of coupling power and signals to a rotating MEMS stage, and measuring its position with much higher accuracy than possible at the macroscale. With this capability, arrays of rotating 100-1000 micron diameter stages could carry various sensors that can be aimed at any azimuth and inclination, and can be rotated 360 degrees for cancelling angle dependent biases. Examples of sensors that might utilize this capability include microphones, antennas, radiation sensors, etc. Although many of these sensors exist, by adding the rotating stage functionality without increase in sensor/system size, weight, and power, one can really see the benefit of integrating MEMS with traditional sensors. The program will transition via industry performers.</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Initiated efforts to implement power and information to microscale rotating stages, for various applications. <p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Develop prototype applications. - Reduce bias levels in sensors, increase directivity in directional sensors, and achieve mechanical phased arrays. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Integrate micro rotating stages with integrated circuits (ICs) to achieve 1-cubic centimeter (cc) microsystem. 						
<p>Chip-Scale Micro Gas Analyzers</p> <p>(U) The Chip-Scale Micro Gas Analyzers program is utilizing the latest microelectromechanical systems (MEMS) technologies to implement separation-based analyzers (e.g., gas chromatographs, mass spectrometers, poly-chromator-like devices) at the micro-scale to greatly enhance the selectivity of sensors to specific species, and thus, enable extremely reliable, remote detection of chemical/</p>						
		9.553	6.433	7.761	0.000	7.761

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B. Accomplishments/Planned Program (\$ in Millions)								
				FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
<p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Investigate active cooling of electronic devices using techniques such as thermoelectric coolers, sterling engines, etc. - Demonstrate a full-performance high-thermal conductivity substrate with enhanced thermal conductivity, hermeticity, and lifetime in a scaled-up 20 cm x 10 cm x <1mm sample. - Scale up prototype air-cooled exchangers to a large, full-format heat sink. - Develop and demonstrate full-sized heat sink using air-cooled exchanger technologies. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Deliver fifty sample thermal conductivity substrate components for testing and insertion into DoD systems. - Design and build modules with all interfaces that demonstrate ACM benefits. - Reduce junction temperature for electronic devices. - Further increase electronic device power. - Increase device reliability. - Identify DoD insertion opportunities, revise testing and reliability activities to meet insertions, and provide testing samples. - Modify parameters of specific DoD insertions. 								
Accomplishments/Planned Programs Subtotals				63.439	77.963	64.496	0.000	64.496
C. Other Program Funding Summary (\$ in Millions)								
N/A								
D. Acquisition Strategy								
N/A								

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E. Performance Metrics

Specific programmatic performance metrics are listed above in the program accomplishments and plans section.

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COST (\$ in Millions)	FY 2009 Actual	FY 2010 Estimate	FY 2011 Base Estimate	FY 2011 OCO Estimate	FY 2011 Total Estimate	FY 2012 Estimate	FY 2013 Estimate	FY 2014 Estimate	FY 2015 Estimate	Cost To Complete	Total Cost
MT-15: <i>MIXED TECHNOLOGY INTEGRATION</i>	122.247	109.131	132.602	0.000	132.602	107.124	106.996	100.106	99.239	Continuing	Continuing

A. Mission Description and Budget Item Justification

(U) The goal of the Mixed Technology Integration project is to leverage advanced microelectronics manufacturing infrastructure and DARPA component technologies developed in other projects to produce mixed-technology microsystems. These ‘wristwatch size’, low-cost, lightweight and low power microsystems will improve the battlefield awareness, security of the warfighter and the operational performance of military platforms. At the present time, systems are fabricated by assembling a number of mixed-technology components: microelectromechanical systems (MEMS), microphotonics, microfluidics and millimeterwave/microwave. Each technology usually requires a different level of integration, occupies a separate silicon chip and requires off-chip wiring, and requires fastening and packaging to form a module. The chip assembly and packaging processes produce a high cost, high power, large volume and lower performance system. This program is focused on the monolithic integration of mixed technologies to form batch-fabricated, mixed technology microsystems ‘on-a-single-chip’ or an integrated and interconnected ‘stack-of-chips’.

(U) The field of microelectronics incorporates micrometer/nanometer scale integration and is the most highly integrated, low-cost and high-impact technology to date. Microelectronics technology has produced the microcomputer-chip that enabled or supported the revolutions in computers, networking and communication. This program extends the microelectronics paradigm to include the integration of heterogeneous or mixed technologies. This new paradigm will create a new class of ‘matchbook-size’, highly integrated device and microsystem architectures. Examples of component-microsystems include low-power, small-volume, lightweight, microsensors, microrobots and microcommunication systems that will improve and expand the performance of the warfighter, military platforms, munitions and Unmanned Air Vehicles (UAVs).

(U) The program includes the integration of mixed materials on generic substrates including glass, polymers and silicon. The program is design and process intensive, using ‘standard’ processes and developing new semiconductor-like processes and technologies that support the integration of mixed-technologies at the micrometer/nanometer scale. The program includes the development of micrometer/nanometer scale isolation, contacts, interconnects and ‘multiple-chip-scale’ packaging for electronic, mechanical, fluidic, photonic and rf/mmwave/microwave technologies. For example, a mixed-technology microsystem using integrated microfluidics, MEMS, microphotonics, microelectronics and microwave components could provide a highly integrated, portable analytical instrument to monitor the battlefield environment, the physical condition of a warfighter, the identity of warfighters (friend or foe) or the combat readiness of equipment. The ability to integrate mixed technologies onto a single substrate will drive down the size, weight, volume, and cost of weapon systems while increasing their performance and reliability.

B. Accomplishments/Planned Program (\$ in Millions)

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B. Accomplishments/Planned Program (\$ in Millions)								
				FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
<p>gyro will have a practical and typical size (~ 4 inch diameter) featuring bias stability and sensitivity (or angle random walk), which is more than 100 times better than state-of-the-art gyroscopes. This program will transition via industry.</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Developed purely single-polarization low-loss, low glass-content BGOF. - Demonstrated compact narrow line-width single-frequency laser technology with ultra-low jitter and the capability of extremely linear frequency scanning. - Developed resonator-ready (low-loss) PCEs for mitigating residual non-linear Kerr Effect errors and relaxing tolerances on laser intensity stabilization requirements. - Developed silicon optical bench technology for optical ruggedization and a path toward a compact and affordable gyroscope. <p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Initiate development of optical bench interface technology for the air-to-bandgap fiber to then be exploited for a gyroscope with reasonable bias performance levels and consistent with military needs. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Demonstrate full gyroscope with integrated electronics and performance exceeding 10 micro-degrees/hr drift. 								
<p>Photonic-enabled Simultaneous Transmit and Receive (P-STAR)</p> <p>(U) Information operation missions on multiple military platforms depend on the ability to transmit and receive radio frequency (RF) signals, simultaneously, from a single aperture. This program will develop transmit/receive modules with high transmit-to-receive isolation and low receive noise figures, over a multi-octave bandwidth, to greatly improve situational awareness of the RF environment, and enable greater control over the information domain. Additionally, the program will develop ultra-wideband (0.1 to 20 Gigahertz (GHz)) photonic components (Photodetectors & Modulators) to significantly enhanced</p>				5.871	7.235	9.512	0.000	9.512

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B. Accomplishments/Planned Program (\$ in Millions)								
				FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
<p>efficiency for applications in antenna Transmit/Receive (T/R) modules. Furthermore, this program will help stem the proliferation of "mission-specific" antennas by providing an ultra-wide bandwidth antenna that can substitute for multiple custom antenna solutions. It is expected that such components would have a significant impact on wideband, multi-functional, multi-beam, Active Electronically Steerable Array antennas by developing modules and detectors that are independently optimized for T/R applications. In addition to the increased functionality, the improved noise figure of the P-STAR technology will increase stand-off ranges and provide improved indications and warning. The program will transition via its industrial performers.</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Fabricated and demonstrated a STAR module which exhibits high T/R isolation over a multi-octave frequency range. - Initiated development of transmit optimized electro-optical transducers and photoreceivers, nominally operating in the 1550 nm band, for operation in the 0.1 to 20 GHz frequency range. <p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Develop and demonstrate low loss lithium niobate optical modulators, which exhibit low switching voltages and incorporate a long effective length for achieving high T/R isolation. - Develop and demonstrate a power amplifier that when connected to the electro-optic modulator and incorporated into the T/R module package, enables the transmit power goal over a multi-octave frequency range. - Enhance third-order intercept point (OIP3) of the Transmit link to +65 decibels (dB) relative to a milliwatt of power (dBm). - Enhance gain of the Receive link to 35 dB. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Enhance output power of the Transmit link to 15 Watts. - Enhance Noise Figure of the Receive link to 3 dB and OIP3 to +43 dBm. 								

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B. Accomplishments/Planned Program (\$ in Millions)

	FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
Gratings of Regular Arrays and Trim Exposures (GRATE)	2.585	12.000	13.490	0.000	13.490
<p>(U) The Gratings of Regular Arrays and Trim Exposures (GRATE) program will develop revolutionary circuit design methodologies combined with hybrid lithography tools to enable cost-effective low volume nanofabrication for DoD applications. Moore's law has driven the silicon industry for several decades with the minimum feature size on an integrated circuit (IC) reduced to 45 nm for today's commercial products. Due to challenging patterning requirements and complex circuit designs, costs of lithography tools and masks have become unaffordable for low-volume manufacture, i.e., military electronics or application specific integrated circuit (ASICs). Similarly, the circuit design, verification, and testing costs have also grown exponentially further preventing military electronics from using advanced silicon technology nodes. Military electronics capabilities are currently limited by the high cost of nanofabrication. To solve this important problem, DARPA has invested in a variety of maskless patterning technologies including parallel e-beam arrays, parallel scanning probe arrays, and an innovative e-beam lithography tool. This program will develop revolutionary circuit design methodologies coupled with innovative hybrid maskless patterning tools to realize cost-effective nanofabrication for low-volume defense or commercial ASICs. Such an approach can also address the nanofabrication requirements of other low-volume DoD technologies such as photonics and micro-electro-mechanical systems. This program will transition via industry.</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Developed 1-D designs and patterning methods. - Evaluated the efficacy of regular geometry templates for improving lithographic performance for more robust imaging, simplified design/layout process, and increased throughput for maskless lithography methods. - Verified efficacy of 1-D design approach. Quantitative benefits of 1-D vs traditional 2-D design approach. 2-D to 1-D conversion of legacy design information processing. - Developed 1-D design enabling process extensions such as "trim/stitch" and "frequency doubling". 1-D test cell fabrication. - Studied feasibility of custom grating fabrication tool based on interference lithography. 					

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B. Accomplishments/Planned Program (\$ in Millions)								
				FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
<p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Develop 1-D fabrication demonstrations. - Develop 1-D standard cell library for digital designs at < 32 nm node. 1-D computer aided design tool development. - 1-D fabrication demos including various circuit elements making use of 1-D specific process extensions. - Demonstrate 1-D circuit patterns using trimmed interference lithography. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Demonstrate grating-based design and fabrication, including experimental verification of desired patterns. The demonstration vehicles will be logic/memory "standard cells" and high speed RF devices in state-of-the-art CMOS technologies. - Develop re-usable grating and trim masks, design methodology, process design kits, and software for layout conversion from standard (2D) to grating-based (1D) layout styles. - Demonstrate wafer-scale patterning of gratings, and the customization of these gratings by the "trim/ stitch" processes. 								
<p>Electromagnetic Pulse Tolerant Microwave Receiver Front End (EMPIRe)</p> <p>(U) The Electromagnetic Pulse Tolerant Microwave Receiver Front End (EMPIRe) program will create a wide bandwidth, tunable RF front end technology that is immune to electromagnetic pulse (EMP) attack. This program will seek an entirely new approach to RF front-end technology where all metal and front-end electronic circuitry are eliminated. Of particular interest will be an all-dielectric, electronics-free RF front end with sensitivity and dynamic range consistent with today's wireless communication and radar systems. A secondary goal is to effect a significant reduction in detectable radar cross section by eliminating the metallic antenna.</p>				5.879	3.070	2.926	0.000	2.926

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B. Accomplishments/Planned Program (\$ in Millions)								
				FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
<p>highly customized, application-specific ICs. In addition, this program will provide a cost effective manufacturing technology for low volume nanoelectromechanical systems (NEMS) and nanophotonics initiatives within the DoD. Transition will be achieved by maskless lithography tools, installed in the Trusted Foundry and in commercial foundries, which will enable incorporation of state-of-the-art semiconductor devices in new military systems, and allow for the cost-effective upgrade of legacy military systems.</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Demonstrated rotary stage at 10 meters per second. - Demonstrated static imaging on prototype Reflective E-Beam Lithograph (REBL) system. - Demonstrated dynamic imaging on prototype REBL system. <p><i>FY 2010 Plans:</i></p> <ul style="list-style-type: none"> - Demonstrate System Level Lithography Performance on a Linear Stage Demonstrator System. - Design, build, and test a rotary stage. - Integrate electron beam column and rotary stage demonstrator platform. - Design, build, and characterize an enhanced electron beam column for system alpha prototype experiments. <p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Design, build, and test an electronic mask device and exercise the data path for design information. - Design and build the next generation Rotary Stage Product Platform Prototype. - Develop and demonstrate a sensitive photoresist with acceptable performance for the 32 nanometer technology requirements. 								
<p>Deep Ultraviolet Avalanche Photodetectors (DUVAP)</p> <p>(U) This program demonstrated avalanche photodiodes (APDs) operating in the Geiger mode, i.e. capable of counting single photons with high gain. The APDs operate in the ultraviolet, in the band</p>				1.139	0.000	0.000	0.000	0.000

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B. Accomplishments/Planned Program (\$ in Millions)

	FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
Precision Navigation (U) The Precision Navigation program goal is to provide compact, rugged, low-power and extremely accurate means for determining position. The resulting systems will provide accurate tools for GPS-denied vehicle operation, on-foot cave and building exploration, precision munitions delivery and many other applications where previous options were too heavy, inaccurate, large or power-hungry. In order to achieve this, sensors will be developed to use internal and external reference information to maximum advantage. One component of the internal type is the development of a new class of microsystems capable of measuring the absolute angle of rotation with the ultra high precision, effectively operating as a mechanical integrator of rotation (MIR). The MIR will not rely on any absolute reference, but will define the reference itself in the absolute inertial space. The device will measure angle of rotation at an unprecedented precision of arc-seconds and a bandwidth in tens of kHz (all characteristics are at least 3 orders of magnitude better than the state-of-the-art). Another component of the program is the development of navigation grade integrated micro gyroscopes with the goal of achieving 0.01 deg/hr bias drift in very compact form factors (less than 1 cm3) and a total power consumption less than 5 mW per sense axis. Another key goal of this program is to harness external references where possible, which can be fused with internally referenced navigation signals to greatly improve performance. One approach to be pursued is the development of miniaturized atomic gradiometer arrays (AGA). Reducing previously bulky and high power AGA's to micro-scales will entail the use of nuclear magnetic resonance phenomena in extremely compact packages for timekeeping, rotation and magnetic field measurements. The AGA's will be deployed in arrays on the order of 10,000 individual sensors, each with the unprecedented target sensitivity of 0.1 femtoTesla (fT). This level of performance will yield not only highly capable navigation instruments making use of local gravitational variations, but also portable devices that are able to detect unexploded bombs/IEDs, camouflaged/faked military assets from platforms such as UAV's. When combined in systems, these new technologies will yield unprecedented navigational capabilities and help deny any advantage for adversaries who might interfere with GPS availability. Technology is expected to transition through industry.	0.000	0.000	7.342	0.000	7.342

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B. Accomplishments/Planned Program (\$ in Millions)

	FY 2009	FY 2010	FY 2011 Base	FY 2011 OCO	FY 2011 Total
<p><i>FY 2011 Base Plans:</i></p> <ul style="list-style-type: none"> - Define miniaturization trade-offs with gyroscope performance to package and ruggedize. - Investigate in-ear plug design that protects ears from damaging sound levels while preserving hearing and sound localization. - Define functional requirements for key micro and nanotechnologies for the sequencer. - Demonstrate surface-enhanced Raman scattering using nanoplasmonic structures. - Demonstrate integration path for light sources and spherical atomic shells in arrays on a single wafer. 					
Accomplishments/Planned Programs Subtotals	115.447	109.131	132.602	0.000	132.602

	FY 2009	FY 2010
<p>Congressional Add: Center for Autonomous Solar Power</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Initiated solar power development. 	4.000	0.000
<p>Congressional Add: Hybrid Power Generation System</p> <p><i>FY 2009 Accomplishments:</i></p> <ul style="list-style-type: none"> - Explored hybrid power technologies including new high-density power generators based on breakthrough configurations of permanent magnet materials, coil designs, and advanced power electronics. 	1.200	0.000
<p>Congressional Add: Ultra Low Power Electronics for Special Purpose Computers/Ubiquitous Computing</p>	1.600	0.000

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B. Accomplishments/Planned Program (\$ in Millions)

	FY 2009	FY 2010
<i>FY 2009 Accomplishments:</i> - Continued low power nano scale electronics development.		
Congressional Adds Subtotals	6.800	0.000

C. Other Program Funding Summary (\$ in Millions)

N/A

D. Acquisition Strategy

N/A

E. Performance Metrics

Specific programmatic performance metrics are listed above in the program accomplishments and plans section.

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